

## **AMENDMENTS TO THE CLAIMS**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

### **Listing of Claims:**

1. (Currently Amended) ~~Device~~ A device for carrying out a plasma enhanced process, ~~in particular a plasma enhanced chemical vapour deposition process, the~~ device comprising within a vacuum chamber a magnetron electrode (32), a positioning means and a gas supply means, the magnetron electrode comprising a flat magnetron face (20) with peripheral and central magnetic poles of opposite polarities and further comprising means for producing a high frequency alternating electric field, the positioning means being equipped for positioning a substrate (25) with a surface to be treated facing the magnetron face (20) and the gas supply means being equipped for supplying a process gas or process gas mixture to the space between the magnetron face (20) and the surface to be treated, ~~characterized in that wherein~~ the magnetron electrode (32) is of the unbalanced type and that a distance between the magnetron face (20) and the positioning means is adapted to the magnetic field created by the magnetron electrode (32) such that there is a visible plasma band running between darker tunnels (11) formed by magnetic field lines (10) extending between peripheral and central magnetic poles of the magnetron face (20) and the surface to be treated, the plasma band having a minimum width but having towards the surface to be treated a homogeneous

brightness.

2. (Currently Amended) ~~Device~~ The device according to claim 1, ~~characterized in that~~ wherein a distance (A-C) between the surface to be treated and the magnetron face (20) is at least 2% larger than ~~the~~ a visible height (A-B) of the tunnels (11).

3. (Currently Amended) The device ~~Device~~ according to ~~claim 1 or 2,~~ ~~characterized in that the~~ claim 1, wherein a distance (A-C) between the surface to be treated and the magnetron face (20) is at ~~the~~ most 20% larger than ~~the~~ a visible height (A-B) of the tunnels (11).

4. (Currently Amended) The device ~~Device~~ according to ~~one of claims 1 to 3,~~ ~~characterized in that the~~ claim 1, wherein a magnetic strength of the central magnetic pole of the magnetron face (20) is about half of ~~the~~ a magnetic strength of the peripheral pole.

5. (Currently Amended) The device ~~Device~~ according to ~~one of claims 1 to 4,~~ ~~characterized~~ claim 1, wherein the magnetron electrode (32) comprises an electrode element (21) being connected to a source of an alternating voltage (34).

6. (Currently Amended) The device ~~Device~~ according to claim 5, ~~characterized in that~~ wherein the positioning means and/or the substrate (25) are arranged to be electrically grounded, electrically floating or negatively biased.

7. (Currently Amended) ~~The device~~ Device according to ~~one of claims 1 to 6,~~  
~~characterized in that~~ claim 1, wherein the positioning means is a rotating drum (30)  
and ~~that wherein~~ a plurality of magnetron electrodes (32) having rectangular faces  
~~being arranged with their length parallel to the rotation axis of the drum (30) are~~  
arranged around part of the ~~a~~ circumference of the drum (30).

8. (Currently Amended) ~~The device~~ Device according to claim 7,  
~~characterized in that~~ wherein the gas supply means comprises gas supply lines (33)  
extending parallel to the drum axis between the magnetron faces (20).

9. (Currently Amended) ~~The device~~ Device according to ~~one of claims 7 or 8,~~  
~~characterized in that~~ claim 7, wherein each of the plurality of magnetrons (32) ~~each~~  
~~magnetron (32)~~ is connected to a separate power supply.

10. (Currently Amended) Use of a ~~the~~ device according to ~~one of claims 1 to~~  
~~9~~ claim 1 for carrying out a plasma enhanced chemical vapour deposition process.

11. (Currently Amended) Use of a ~~the~~ device according to ~~one of claims 1 to~~  
~~9~~ claim 1 for depositing silicon oxide using a process gas comprising an  
organosilicon compound and oxygen.

12. (Currently Amended) Use according to claim 11, ~~characterized in that~~  
wherein the substrate is a web of polymer film material being coated so as to

improve ~~for improving its barrier properties~~ of said web of polymer film material.